

ID-MARK PROCESSING TIPS & HINTS

PROBLEM: Part or all of the image is lost during rinsing.

Cause: Sheet is under-exposed, resist not hardened enough.

Solution: Exposure time needs to be increased.

Cause: Too much pressure exerted when wiping and rinsing off resist.

Solution: Use only light pressure. Let the cotton pad and water do the work.

Cause: Poor contact between film and ID-MARK sheet during exposure.

Solution: Contact must be extremely close between ID-MARK material and film during exposure.

Cause: Not enough contrast between clear and opaque areas on film.

Solution: Artwork images must be opaque, but the actual film needs to be clear.

Cause: Wrong type of exposure device.

Solution: Light source must be ultra-violet (black light). Incandescent light sources (such as office copiers) will not work.

Cause: Photosensitive side on the ID-MARK material is facing away from the light during exposure.

Solution: The photosensitive side (colored side) needs to face the light during exposure.

Case: Emulsion side on the film is not in contact with the photosensitive side on the ID-MARK material.

Solution: Use film with emulsion or toner on the film in contact with the photosensitive (colored) side on the ID-MARK material.

Case: Leaving water on the sheet too long.

Solution: ID-MARK will process without a great deal of water. Soaking the sheet with too much water will cause all the resist to soften and wash away.

PROBLEM: Double or fuzzy images appear during processing.

Cause: Film (artwork) shifted during exposure.

Solution: This can happen if the film and the ID-MARK material are not held in extremely close contact during exposure.

Cause: Film was printed with emulsion side up. Resulting light diffusion caused shadows or double images.

Solution: Film needs to be printed so that it is right-reading photosensitive side of sheet.

PROBLEM: Pinholes or voids appear on correctly exposed ID-MARK material.

Cause: Dirt or lint on cover glass of exposure device.

Solution: Clean glass.

Cause: Dirt or lint on film.

Solution: Clean off film with lint free cloth.

PROBLEM: No image appears at all.

Cause: Sheet is overexposed.

Solution: Reduce exposure time. Ensure opaque (black) areas on film are dark enough to hold back light.

Cause: Art (film) images are not opaque enough to block the light during exposure.

Solution: Film must be transparent, but the artwork images must be opaque.

Cause: Material exposed before use.

Solution: Store unexposed material in sealed black pouch when not in use.

PROBLEM: Scratches on correctly exposed ID-MARK material.

Cause: Too abrasive a pad used in rinsing and wiping off resist.

Solution: A Soft, lint-free cotton pad, such as an AppliPad (Part #7020 should be used in rinsing and wiping off the emulsion. Do not use paper towels or facial tissues.

Cause: Fingernails or rings make contact with resist when wet.

Solution: Make certain that only the cotton pad comes in contact with the ID-MARK material while it is wet.